



News from Plasma-Therm
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Plasma-Therm introduces new Quasar™ IBE System

ST. PETERSBURG, Fla. Sept 9th, 2019 — Plasma-Therm LLC has introduced a new Quasar™ Ion Beam Etch System for advanced Ion Beam Etch (IBE) with enhanced capability.

The Quasar™ IBE system incorporates a unique feature of planetary scanning technology – the ability to sweep the wafer in an oscillatory manner across the ion beam.

Dr. Ming Mao, Engineering Director of Advanced Process Development at Western Digital Corp said, *“With the introduction of Plasma-Therm’s Quasar™ system, which incorporates the unique feature of planetary scanning technology, their innovative Marathon™ Ion Source and Fast Motion Control scanning, Plasma-Therm has produce a truly leading edge technology that provides long term etch uniformity, etch rate stability and process fulfilling the requirements of next generation of IBE technology.”*

Hari Hedge, Plasma-Therm’s Business Unit Manager for Ion Beam technology said, *“We are pleased to have completed the acceptance of the Quasar™ IBE system. This next generation IBE system provides a full order of magnitude improvement in etch uniformity and feature profile compared to typical broad-beam IBE technology”.*

About Plasma-Therm

Plasma-Therm LLC is a manufacturer of leading plasma etch, deposition, and advanced packaging equipment for specialty semiconductor and nanotechnology markets. Plasma-Therm's plasma-processing and advanced-packaging solutions are used in research, pilot manufacturing, and volume production of wireless, photonics, solid state lighting, MEMS/NEMS, data storage and other devices. Learn more at www.plasmatherm.com.

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